

	Type	L #	Hits	Search Text	DBs
1	IS&R	L1	1	("7030452").PN.	USPAT
2	BRS	L2	135	tunnel\$6 near6 current same gap same voltage near6 bias	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	46	tunnel\$6 near6 current same gap same voltage near6 bias same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
4	BRS	L4	2	tunnel\$6 near6 current same gap same voltage near6 bias same electrode same membrane	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
5	BRS	L5	7	2 and membrane	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L6	4	2 and membrane same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
7	BRS	L8	3	2 and ion near6 beam same gap	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
8	BRS	L9	3	2 and ion near6 beam same (gap or channel or microchannel or aperture) same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
9	BRS	L7	14	2 and ion near6 beam	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
10	BRS	L10	3	tunnel\$6 near6 current same gap same voltage near6 bias same ion near5 beam	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
11	BRS	L11	74	tunnel\$6 near6 current same ion near5 beam	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L12	6825	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal)	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
13	BRS	L13	2	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same electrode same tunnel\$6 near5 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
14	BRS	L14	4	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same tunnel\$6 near5 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L15	528	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
16	BRS	L16	17	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same electrode near6 gap	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
17	BRS	L17	0	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same electrode near6 gap same tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
18	BRS	L18	0	ion near5 beam near5 (mill or milling or drill or drilling or lithography or removal) same electrode near6 gap and tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	9580	ion near6 beam with (electrode or nanoelectrode)	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
2	BRS	L2	229	ion near6 beam with (electrode or nanoelectrode) near6 (spacing or gap)	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
3	BRS	L3	1204	ion near6 beam with (electrode or nanoelectrode) same etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
4	BRS	L4	861	ion near6 beam with (electrode or nanoelectrode) with etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
5	BRS	L5	49	4 and tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
6	BRS	L7	0	6 and tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B



	Type	L #	Hits	Search Text	DBs
7	BRS	L6	9	ion near6 beam with (electrode or nanoelectrode) with etch\$6 same (raster\$6 or blanket)	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
8	IS&R	L8	1	("5071832").PN.	USPAT
9	BRS	L9	1061	ion near6 beam same raster\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
10	BRS	L10	652	ion near6 beam with raster\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
11	BRS	L12	19	ion near6 beam with blanket same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
12	BRS	L13	1	11 and 12	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
13	BRS	L11	85	ion near6 beam with raster\$6 same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
14	BRS	L14	1061	electron near6 beam with raster\$6 same electrode	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
15	BRS	L15	562	electron near6 beam with (electrode or nanoelectrode) with etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
16	BRS	L16	16	15 and tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
17	BRS	L17	29777	electron near6 beam with (electrode or nanoelectrode)	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
18	BRS	L18	326	17 and tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
19	BRS	L19	27	electron near6 beam with (electrode or nanoelectrode) same tunnel\$6 near6 current	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
20	BRS	L20	6	electron near6 beam with (electrode or nanoelectrode) same tunnel\$6 near6 current same etching	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
21	BRS	L21	9	beam with (electrode or nanoelectrode) same tunnel\$6 near6 current same etching	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
22	BRS	L22	13	beam same (electrode or nanoelectrode) same tunnel\$6 near6 current same etching	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
23	BRS	L23	21	beam same (electrode or nanoelectrode) same tunnel\$6 near6 current same etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
24	BRS	L24	12	beam same (electrode or nanoelectrode) same tunnel\$6 near6 current same lithography	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
25	BRS	L25	9797	beam same (electrode or nanoelectrode) same etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B

	Type	L #	Hits	Search Text	DBs
26	BRS	L26	2432	beam with (electrode or nanoelectrode) with etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
27	BRS	L27	243	(electrode or nanoelectrode) same tunnel\$6 near6 current same etch\$6	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B
28	BRS	L28	2	(electrode or nanoelectrode) same tunnel\$6 near6 current same etch\$6 same work near6 function	US- PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWEN T; IBM_TD B